

	<b>Hits</b>	<b>Search Text</b>	<b>DBs</b>
<b>14</b>	0	(IC or (integrated near5 circuit\$4)) and ((open\$4 or etch\$4 or remov\$4 or blow\$4 or ablat\$4 or (delet\$4 near9 laser)) same fuse) and (fuse same (metal\$4 or conduct\$4 or Cu or copper)) and (terminal or interconnect\$4) and ((non\$4last or second\$4last or (L near2 minus near2 one)) near16 (metal\$4 or conductive) near20 fuse) and (barrier or (diffus\$4 near5 barrier)) and (etch\$4 same (dry or wet)) and ((resist or photoresist) same (expos\$4 or illuminat\$4 or irradiat\$4)) and develop\$4 and pattern\$4	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT; IBM_TDB
<b>15</b>	0	(IC or (integrated near5 circuit\$4)) and ((open\$4 or etch\$4 or remov\$4 or blow\$4 or ablat\$4 or (delet\$4 near9 laser)) same fuse) and (fuse same (metal\$4 or conduct\$4 or Cu or copper)) and (terminal or interconnect\$4) and ((non\$4last or second\$4last or (L near2 minus near2 one)) near16 (metal\$4 or conductive) near20 fuse) and (barrier or (diffus\$4 near5 barrier)) and (etch\$4 same (dry or wet)) and ((resist or photoresist) same (expos\$4 or illuminat\$4 or irradiat\$4)) and develop\$4 and pattern\$4	US-PGPUB

	<b>Hit s</b>	<b>Search Text</b>	<b>DBs</b>
<b>16</b>	0	(IC or (integrated near5 circuit\$4)) and ((open\$4 or etch\$4 or remov\$4 or blow\$4 or ablat\$4 or delet\$4) same laser same fuse) and (fuse same (metal\$4 or conduct\$4 or Cu or copper)) and (terminal or interconnect\$4) and ((non\$4last or second\$4last or (L near2 minus near2 one)) near16 (metal\$4 or conductive) near20 fuse) and (barrier or (diffus\$4 near5 barrier)) and (etch\$4 same (dry or wet)) and ((resist or photoresist) same (expos\$4 or illuminat\$4 or irradiat\$4)) and develop\$4 and pattern\$4	US-PGPUB
<b>17</b>	0	(IC or (integrated near5 circuit\$4)) and ((open\$4 or etch\$4 or remov\$4 or blow\$4 or ablat\$4 or delet\$4) same laser same fuse) and (fuse same (metal\$4 or conduct\$4 or Cu or copper)) and (terminal or interconnect\$4) and ((non\$4last or second\$4last or (L near2 minus near2 one)) near16 (metal\$4 or conductive) near20 fuse) and (barrier or (diffus\$4 near5 barrier)) and (etch\$4 same (dry or wet)) and ((resist or photoresist) same (expos\$4 or illuminat\$4 or irradiat\$4)) and develop\$4 and pattern\$4	US-PGPUB; USPAT; FPRS; EPO; JPO; DERWENT